



Chalk River Tritium Activities: Select Topics

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Tritium Focus Group Meeting, Princeton, NJ, 2015 May



Topics

- **Canadian Nuclear Labs – former AECL**
- **New Tritium Facility**
- **Tritium-resistant e-cell materials**
- **Beta-voltaics**
- **Helium-3 recovery**



Chalk River Labs

- **Main campus of Canadian Nuclear Labs – former AECL**
- **Established 1952 Crown Corporation**
- **3100 employees (500 advanced degrees)**
- **600 M\$ in revenue and funding**
- **9000 acres in Ontario, next to the Ottawa River**



Restructuring Canadian-style

GOCO model (government owned, company operated).

AECL split: AECL(crown) + CNL(corporation)

- **CNL corporate entity sold to private company with operating contract (term)**
- **AECL represents Government to manage operating contract and retain ownership of physical assets and liabilities**



Restructuring Canadian-style (cont.)

- **Private operator selected May, transfer October**
- **Bidders:**
 - **ICA – Babcock & Wilcox, Cavendish Nuclear & Battelle Memorial Institute**
 - **CNEA – Energy Solutions, CH2M Hill, Kinectrics, Lockheed Martin & SNC Lavalin**
 - **CNRP – Golder, Bechtel GCSC & Hatch**
 - **NNLA – URS corporation, McMaster U & Ontario Power Generation**



CNL Tritium Facility

- Set up before 1980
- One-of-a-kind in Canada
- Six R&D Labs in an old building
- Commercial and R&D Operations
- Handles up to 1 MCi T₂ (100 g)
- Tritiated water to 1000 Ci/kg
- 15 technical staff



New Tritium Laboratories

Mechanical / Office Building

Service / Laboratory Building

Process Building

Shipping / Receiving



New Tritium Laboratories



New Tritium Laboratories

- Two inert atmosphere glove boxes (IAGB) – dispensing, CECE-T
- Gas standards preparation fumehood (FH)
- Cylinder paint booth and conditioning booth
- Air-purged GBs (maintenance)
- Gas sampling FH
- Tritium assay FH
- Tritium counting room
- Tritium storage vault
- Gas storage areas
- 15 general use FHs (three active drains)



T-resistant PEM-Cell Materials

- New proton-exchange membrane materials capable of retaining integrity and performance in high-tritium environment
- Demonstrate full-scale cell with new materials
- Nafion is most widely-used, breaks down with 100 kGy
- Two new membrane materials developed at Chalk River show promise at >100 kGy
- Initial exposure tests in 1000 Ci/kg water show improved tolerance for new materials
- Tests in full-scale e-cell requires exposure followed by decontamination and this has been difficult – tritium is strongly bound to membrane



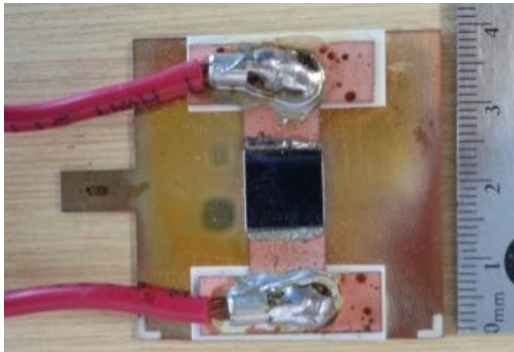
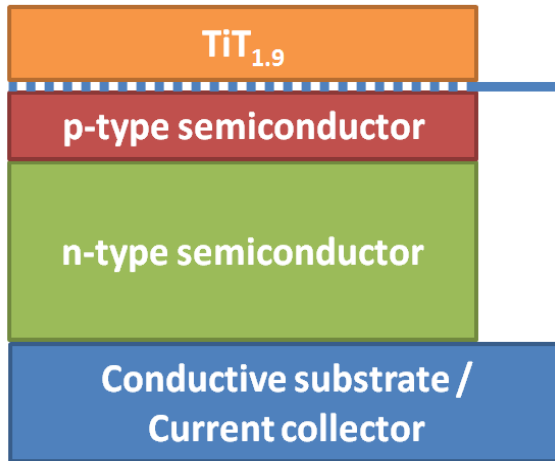
Tritium-Powered Batteries

- **Use of tritium decay-energy as power source**
- **Convert high-energy electrons into low-voltage current**
- **Two methods:**
 - **Indirect: beta \rightarrow photons \rightarrow conduction electrons**
 - **Direct: beta \rightarrow conduction electrons**

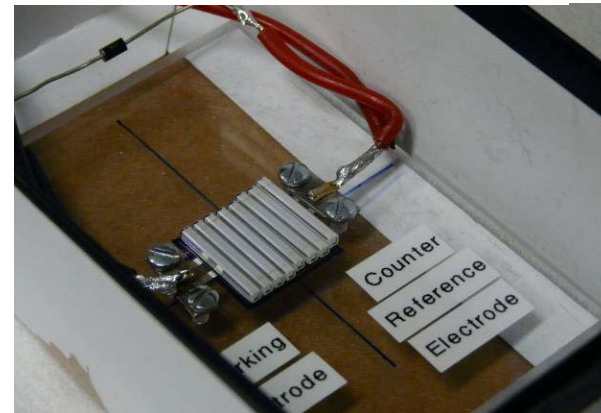
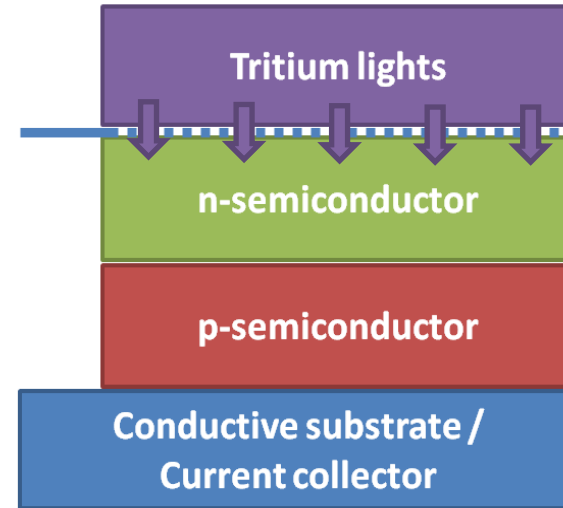


Tritium-powered batteries

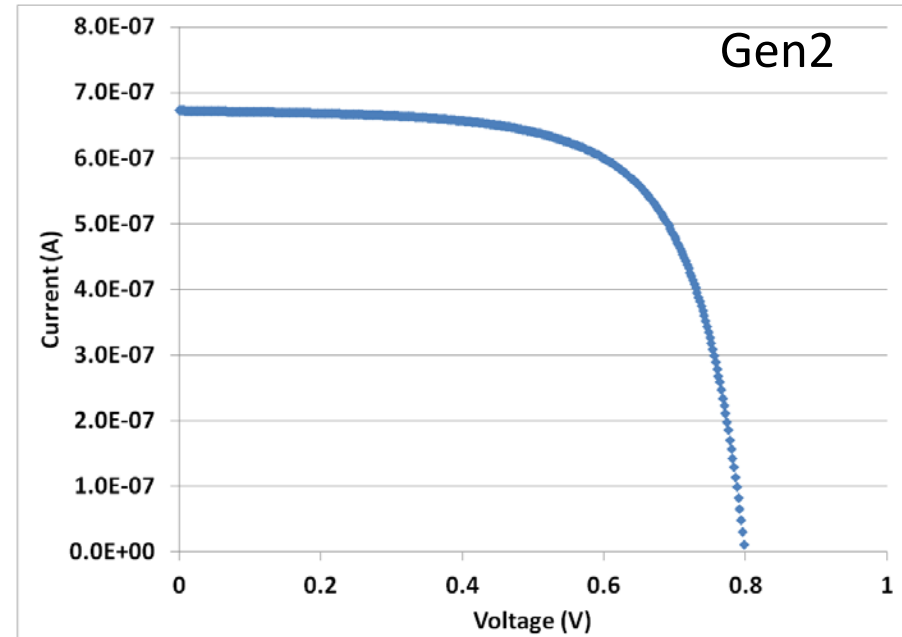
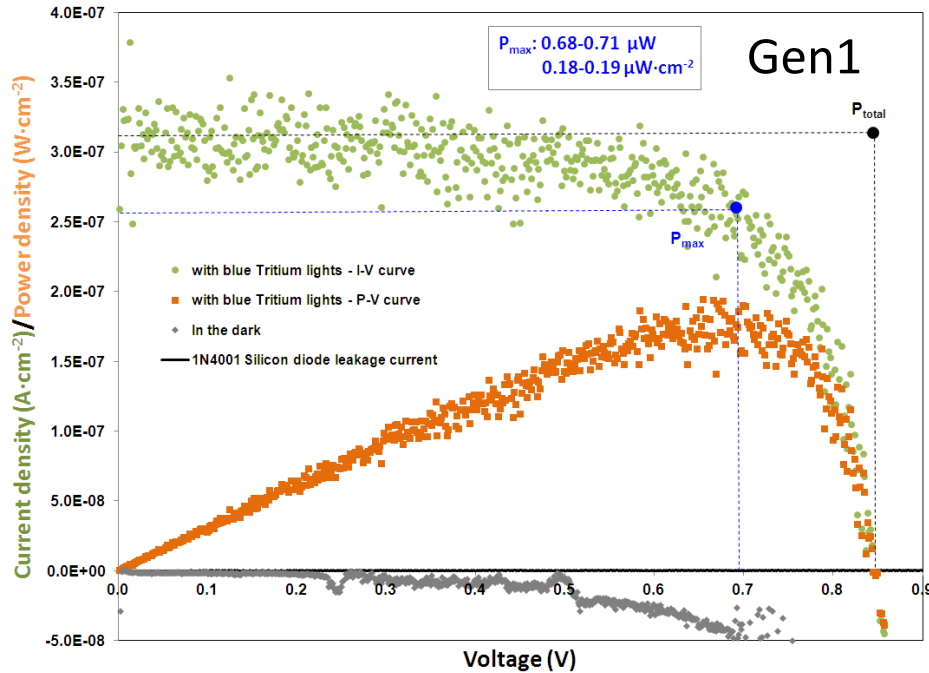
Direct Conversion



Indirect Conversion



Indirect Tritium battery-Tritium lights plus photocell

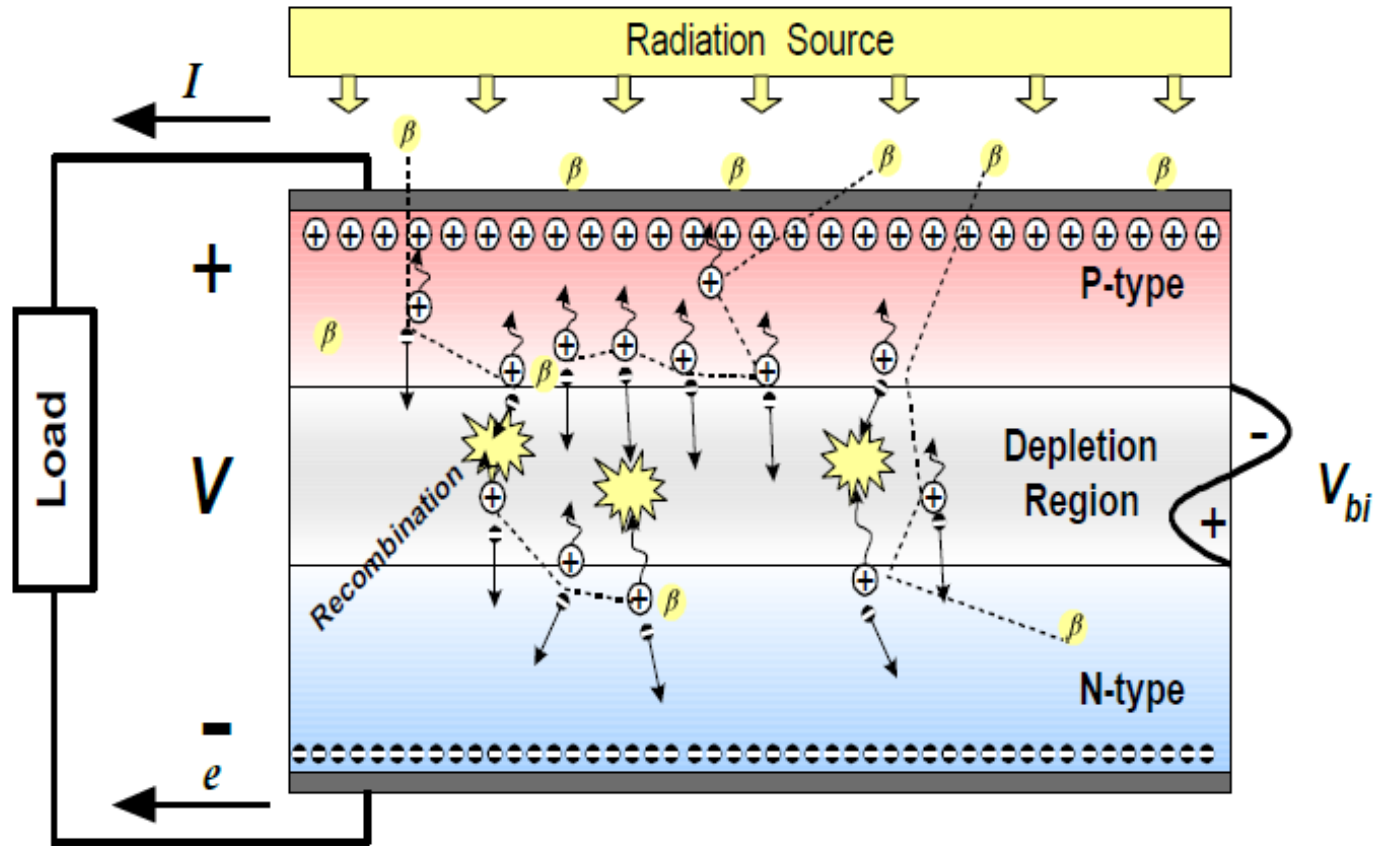


- Cells degraded on repeated exposure to tritium, dead after ~ 10 hours

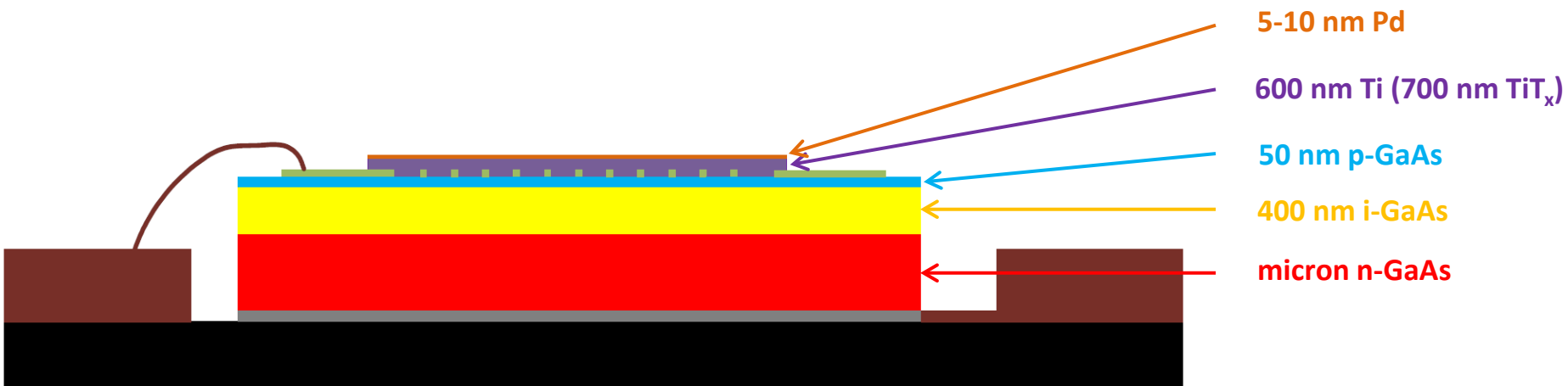
- Max power: $0.4 \mu W$, $0.1 \mu W/cm^2$
- About 4 Ci tritium
- No loss in several days












Direct Tritium battery-Immobilized Tritium Layers

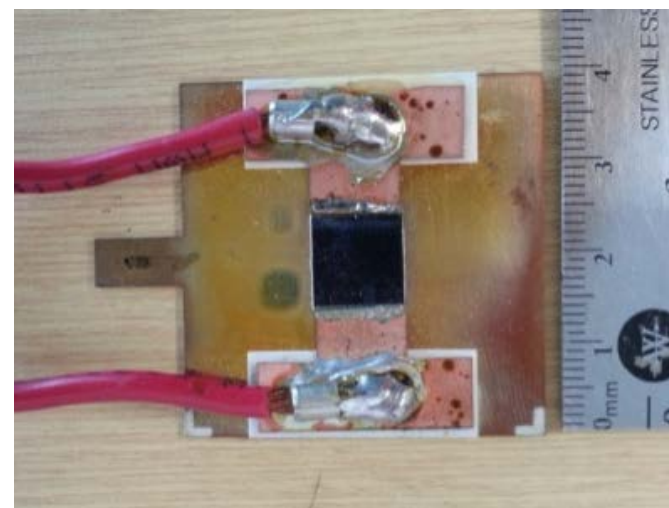


Direct Tritium battery

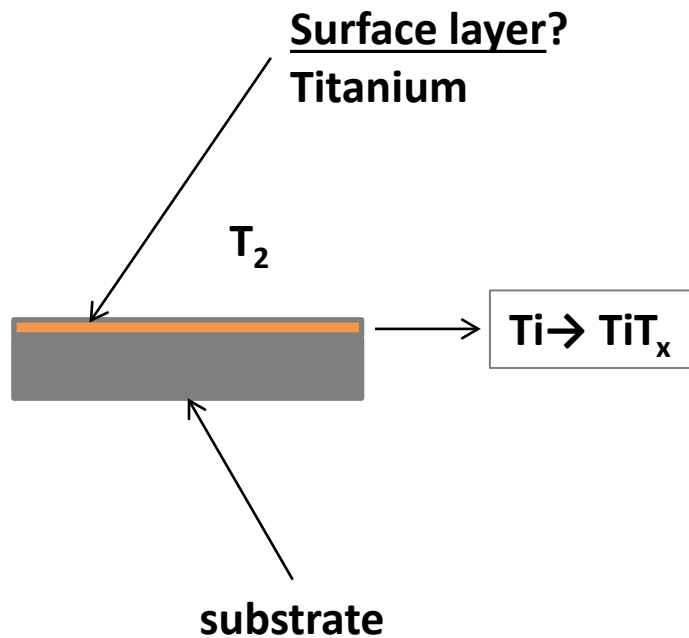


Legend:

 Packaging base plate	 GaAs i type	 Ti
 N contact	 GaAs p type	 Pd
 GaAs n type	 P contact	 Contact pads (Au or Al)



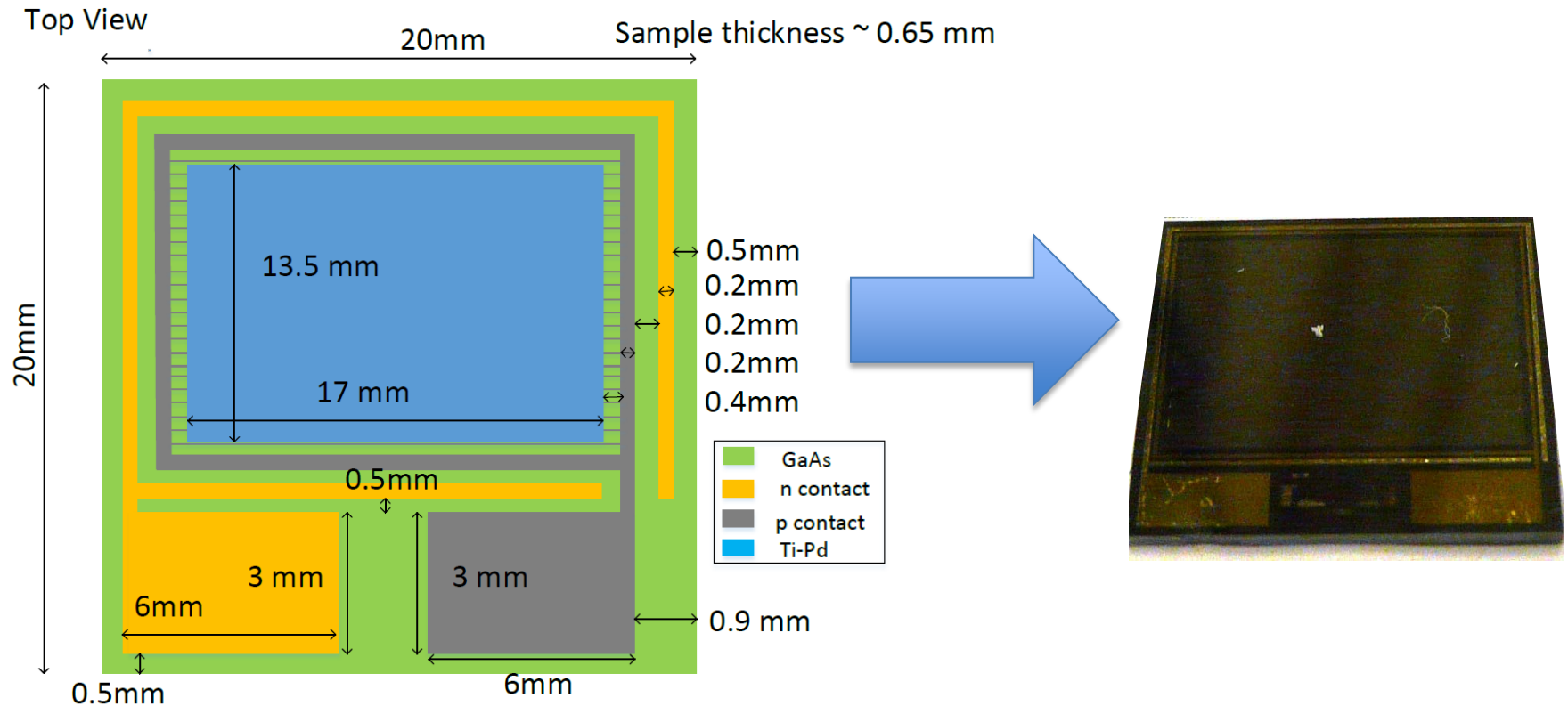
Direct Tritium battery-Immobilized Tritium Layers



Metal
vapour
deposition



Sample Design



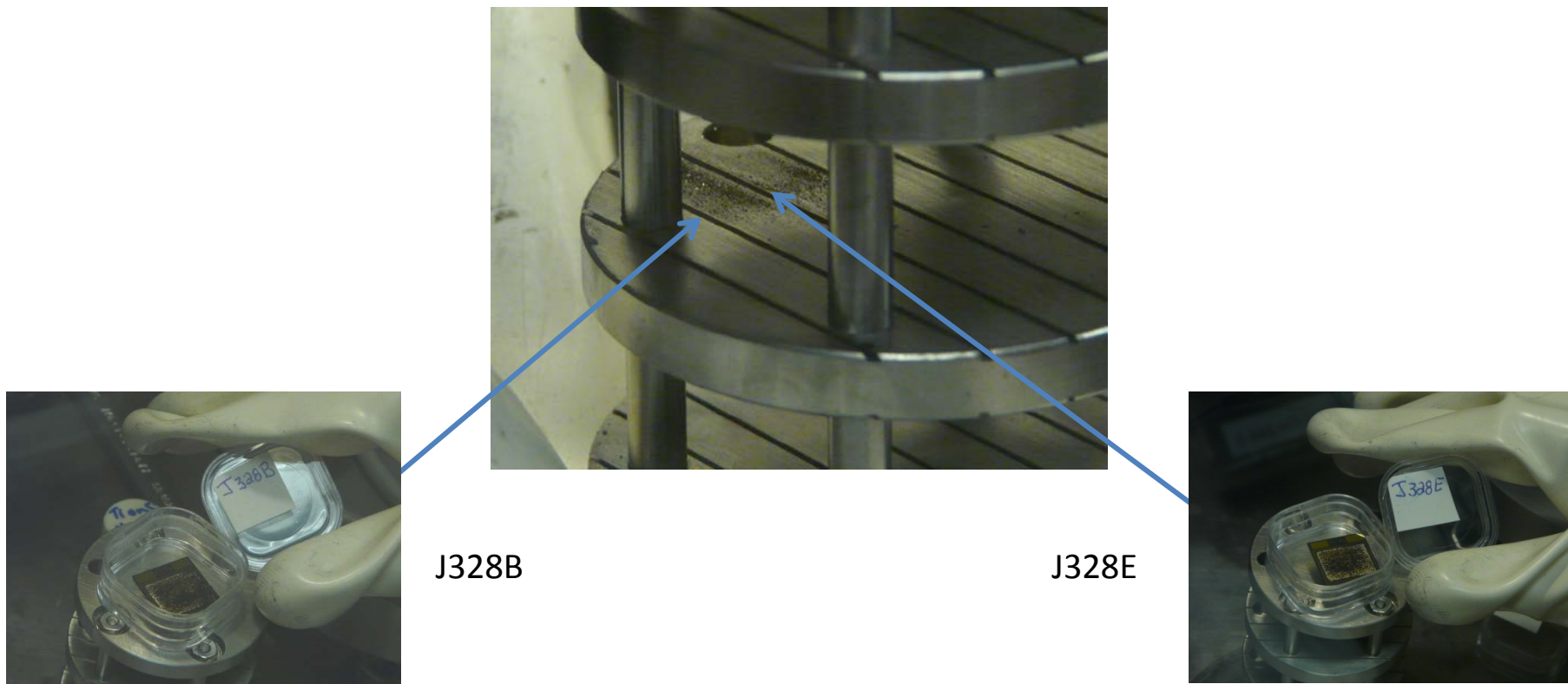
- GaAs substrate
- Large contacts for clips



Samples and Vessel



Delamination of Titanium Metal

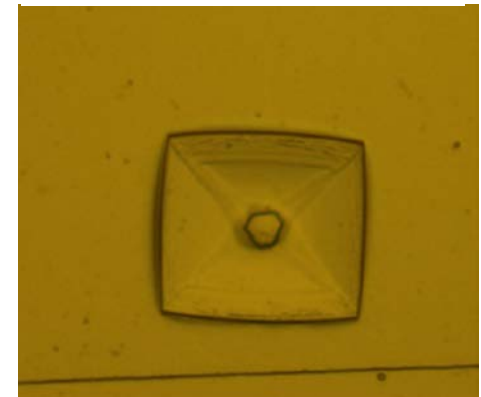
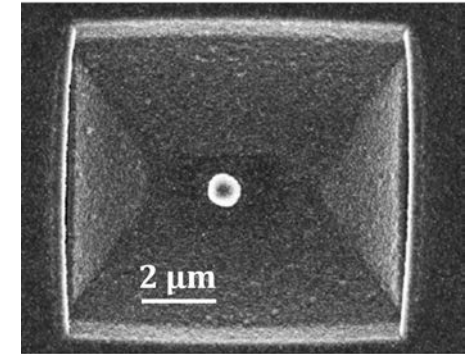


Flecks of metal left behind in sample holder from these two samples

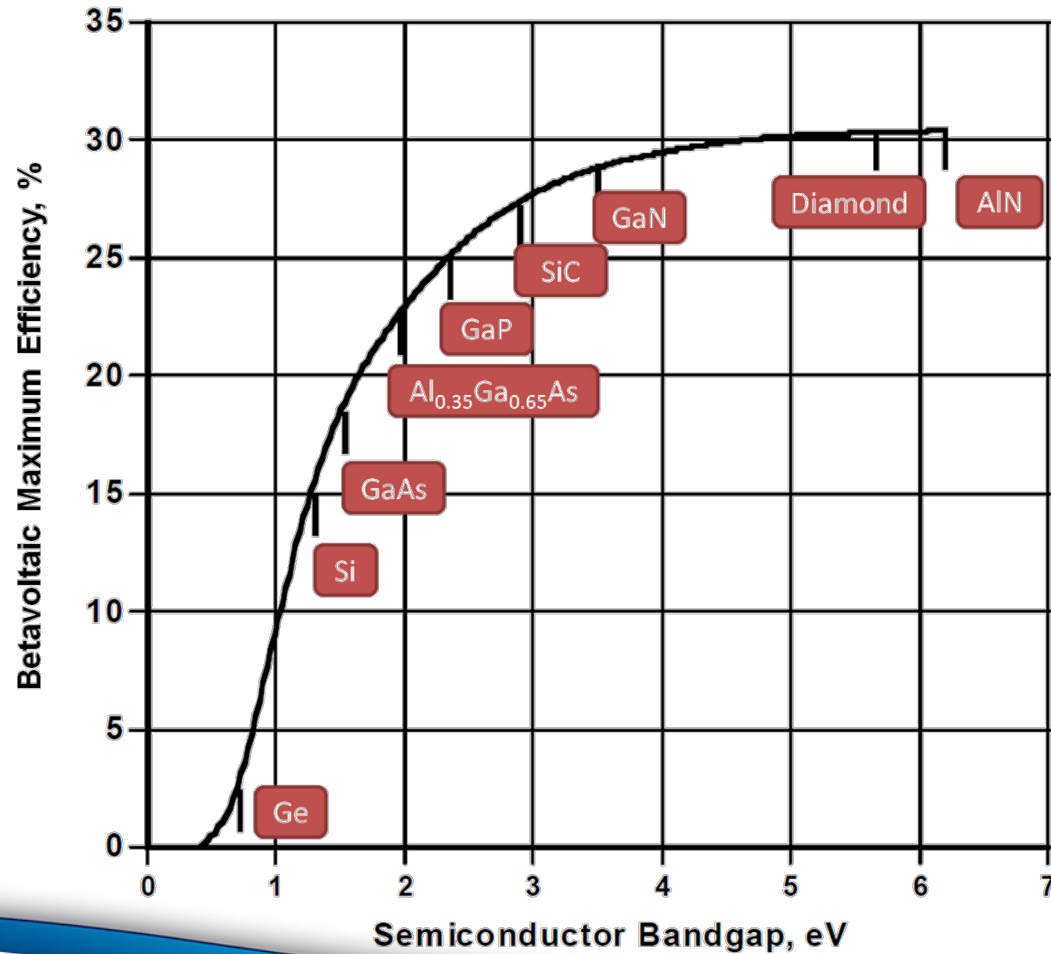


Betavoltaic “Pitfalls”

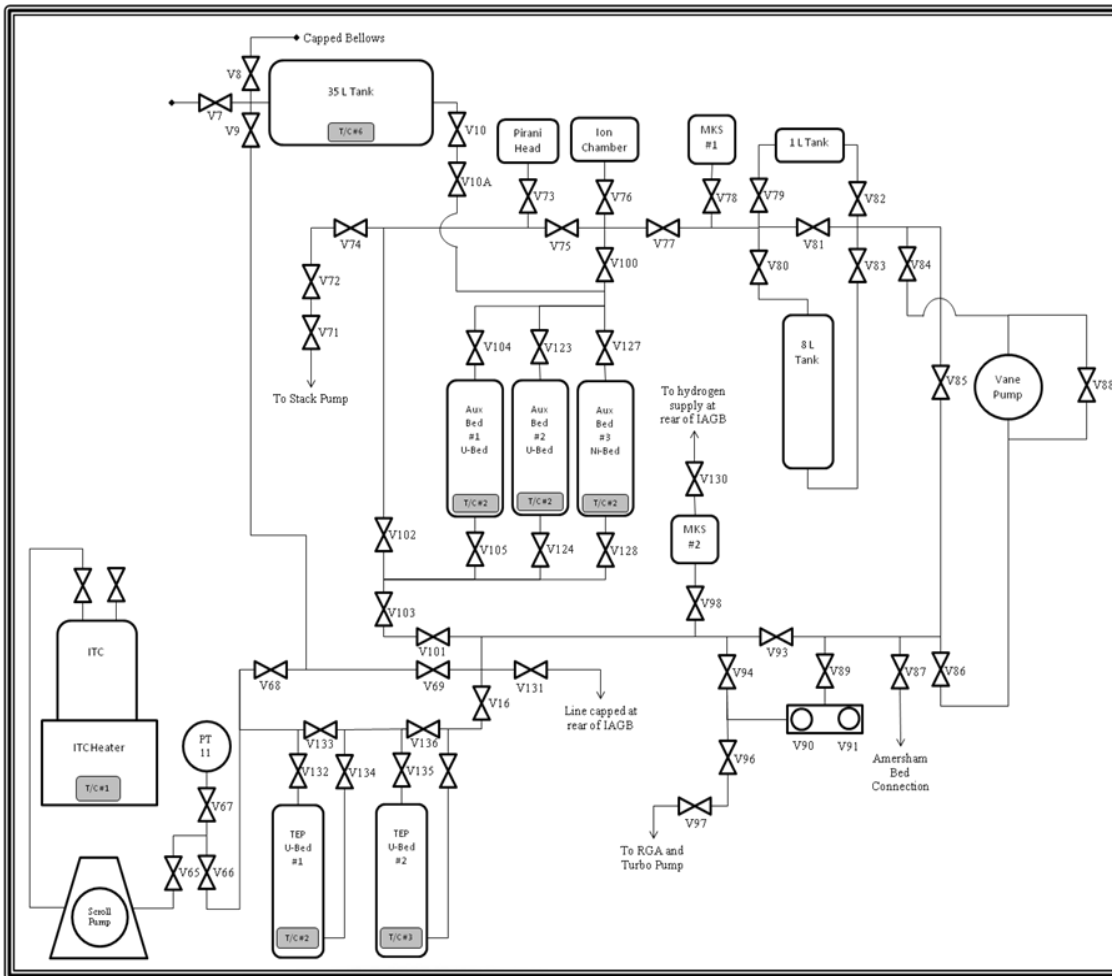
- Large pits (up to $10\ \mu\text{m} \times 10\ \mu\text{m}$) form in the GaAs wafers after multiple etching steps, short circuits with Ti layer
- Thin stabilizing oxide layer to minimize damage from etching
- Materials which are resistant to chemical etching such as GaN or SiC



Choice of Semiconductor by Bandgap



Helium-3 recovery

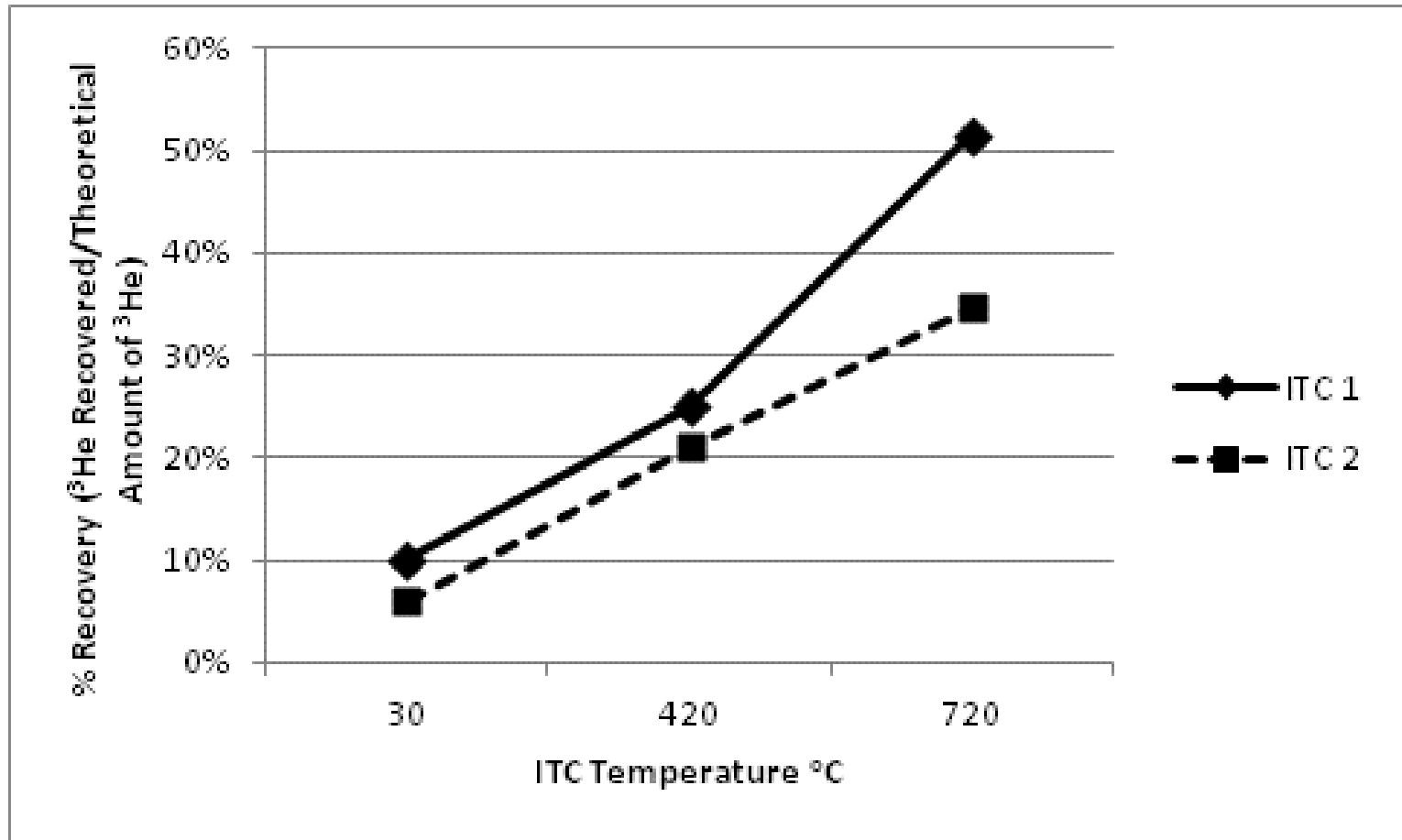


- Heat ITCs to ?
- Determine He-3 recovery as function of temperature
- Determine recovery as function of decay time
- Determine if a one-step purification can be effective
- Determine best means of collecting and storing He-3



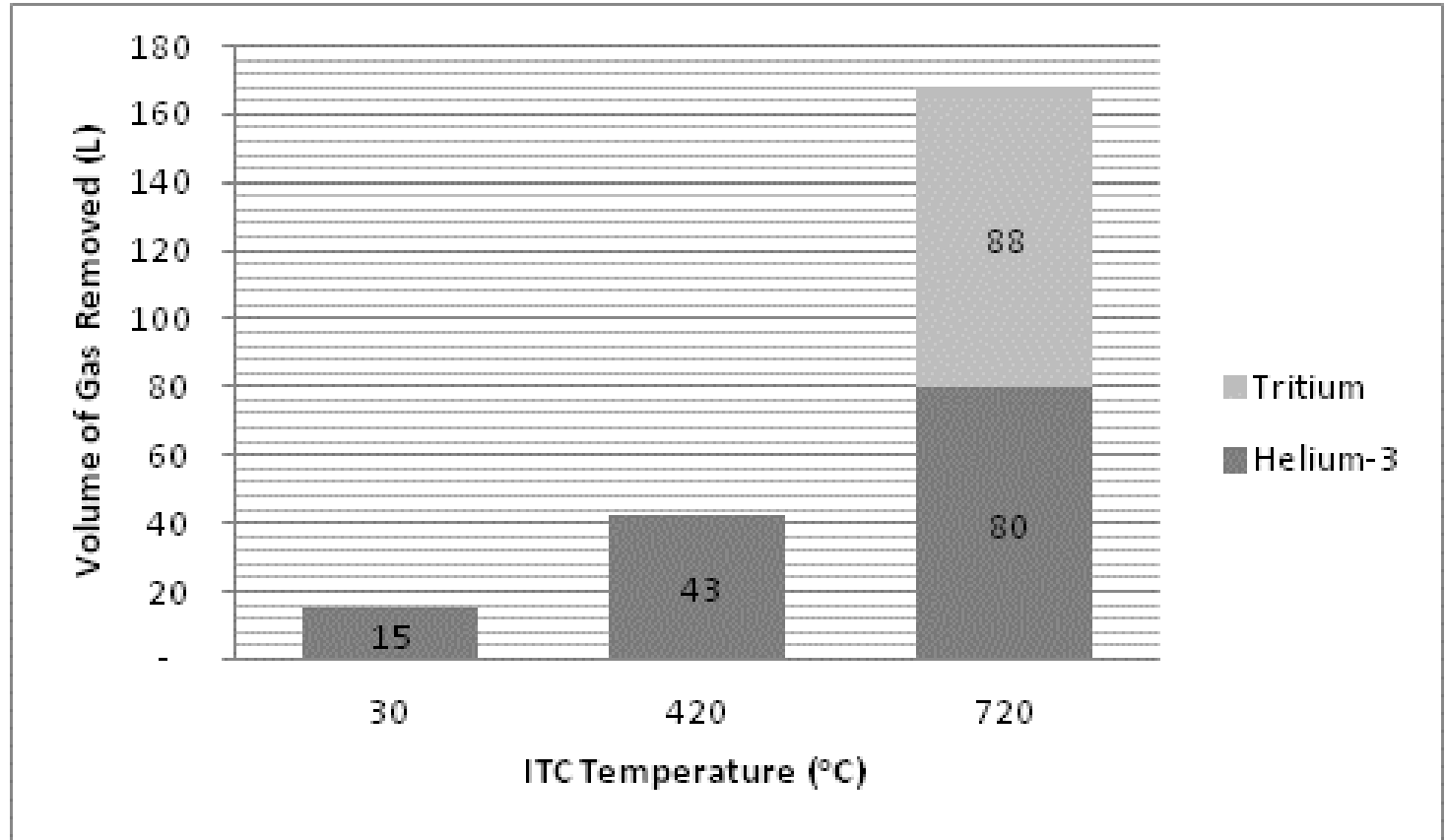
Helium-3 recovery from ITCs

8 years
decay
measured
recovery



Helium-3 recovery from ITCs

12 years
decay
estimated
recovery



Helium-3 purification

- **Minimum steps to clean up He-3 for use:**
 - **In-house (non-hazardous)**
 - **For general sale (free-release)**
- **After heating, see tritiated methane, water, ammonia(?)**
- **Current work to investigate cleanup and storage**





Thank you - Merci



Canadian Nuclear Laboratories | Laboratoires Nucléaires Canadiens

UNRESTRICTED/ ILLIMITÉ -26-

Main IAGB

